1 We claim: 1 1. A method of measurement of topographic features on a surface of a substrate, comprising: 2 a) directing a focused beam of particles to fall at a first angle  $\theta_1$  on to a first portion of the 3 surface of the substrate, where  $\theta_1$  is defined with respect to an average normal to the 4 surface of the substrate; 5 b) detecting particles emitted from the first portion of the surface of the substrate at a second 6 angle  $\theta_2$ , where  $\theta_2$  is defined with respect to the average normal to the surface of the 7 substrate, the particles detected with a particle detector; 8 c) interposing a particle opaque material between the first portion of the surface of the substrate 9 and the particle detector, the particle opaque material having an edge; 10 d) determining the relative position of the edge and the first portion of the surface of the 11 substrate from the results of the detection of particles. 1 2. The method of claim 1, where the particles of the focused beam of particles are charged 2 particles. 1 3. The method of claim 2, where the charged particles are electrons. 1 4. The method of claim 2, where the charged particles are ions. 1 5. The method of claim 1, where the particle opaque material is separate from the substrate.

6. The method of claim 5, further comprising: 1 e) directing the focused beam of particles on to a plurality of portions of the surface of the 2 3 substrate; then, f) determining the topographic features of the plurality of portions of the surface from the results 4 of the detection of particles. 5 7. The method of claim 6, wherein the topographic features of the plurality of portions form a 1 trench in the substrate, and wherein the trench and the edge form an angle significantly 2 3 greater than 0°. 8. The method of claim 7, wherein the topographic features of the plurality of portions form a 1 trench in the substrate, and wherein the trench and the edge form an angle approximately 2 90°. 3 9. The method of claim 8, wherein the trench in the substrate has sidewalls which are 1 approximately parallel to the average normal to the surface of the substrate. 2 10. The method of claim 1, further comprising: 1 e) repeating steps a-d with at least one of the angles  $\theta_1$  and  $\theta_2$  changed. 2 11. The method of claim 10, further comprising determining the parameters of the focused 1 particle beam wherein the focused particle beam is focused on the surface of the 2 3 substrate. 12. The method of claim 1, wherein the particle opaque material between the first portion of 1

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the surface of the substrate and the particle detector is a portion of the substrate.

1 13. The method of claim 12, further comprising: e) directing the focused beam of particles on to a plurality of portions of the surface of the 2 3 substrate; then, f) determining the topographic features of the plurality of portions of the surface from the results 4 5 of the detection of particles. 1 14. The method of claim 13, further comprising: 2 e) repeating steps a-f with a change of the angle  $\theta_i$ . 1 15. The method of claim 13, wherein

the plurality of portions of the surface of the substrate are portions of the surface of a trench in

the substrate, and the edge is an edge of the trench.

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